

# Influence of Fermi-level on the lattice location of $^{27}\text{Mg}$ in GaN

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**(Emission Channeling with Short-Lived Isotopes,  
the EC-SLI collaboration)**

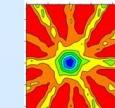
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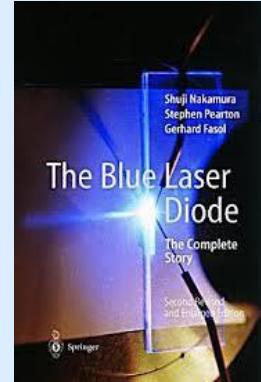


**EC-SLI**  
uses

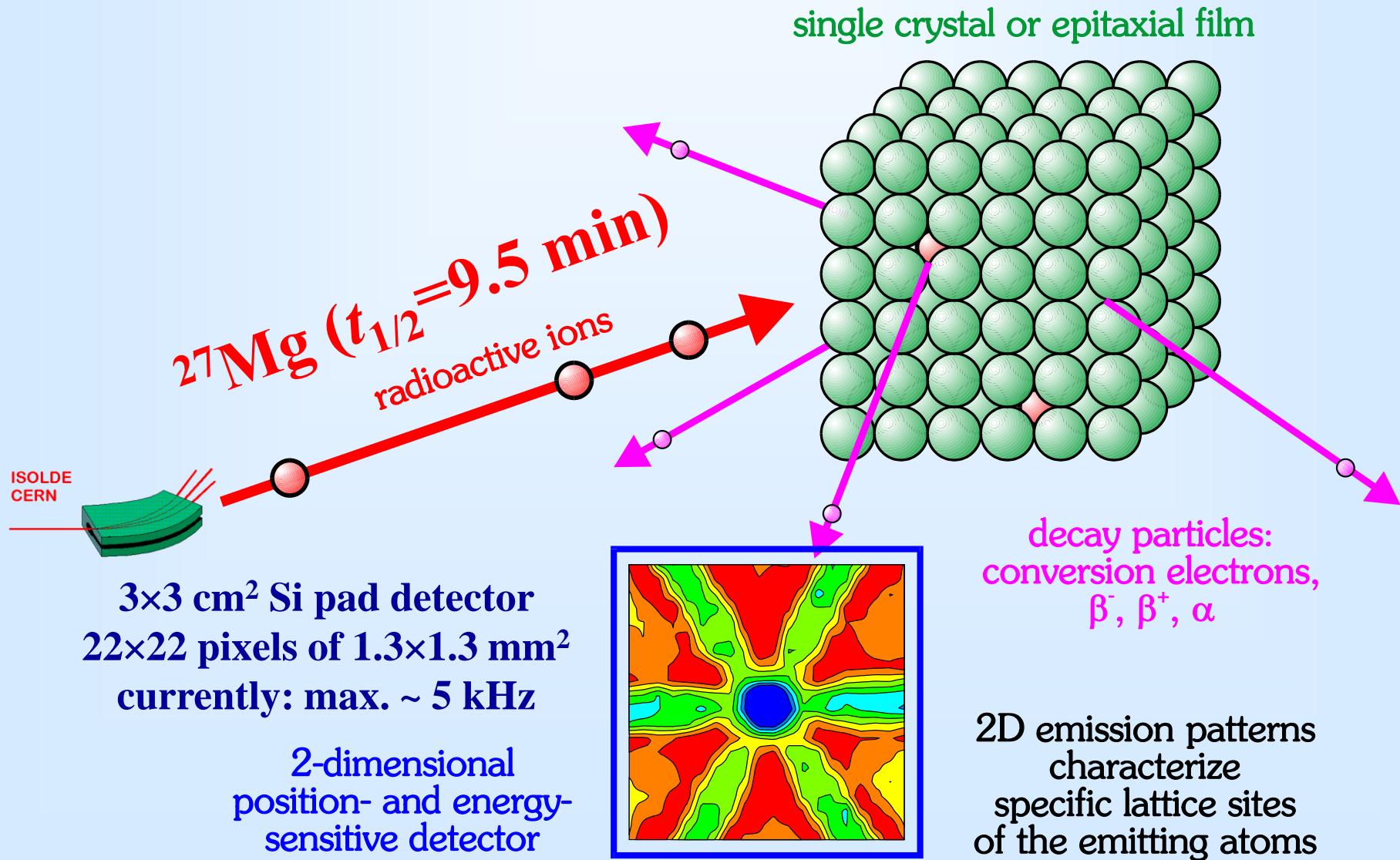
# Motivation: Mg in nitride semiconductors

- Nitrides are base material e.g. for white LEDs, blue lasers, power devices, voltage transformers
- Mg is the only technologically relevant *p*-type dopant in GaN
- To be electrically active, Mg acceptors (group II) should occupy substitutional Ga (group III) sites
- However, if  $[Mg] > 10^{20} \text{ cm}^{-3}$ , Mg becomes inactive
- Emission channeling experiments at ISOLDE were the first to reveal also interstitial Mg sites

Nobel prize in Physics 2014  
I. Akasaki,  
H. Amano,  
S. Nakamura



# Emission channeling: basic principle



# Direct evidence for amphoteric nature of Mg in GaN

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PHYSICAL REVIEW LETTERS

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3 MARCH 2017

## Lattice Location of Mg in GaN: A Fresh Look at Doping Limitations

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- [0001] emission channeling patterns quantify implanted interstitial  $^{27}\text{Mg}_i$  with accuracy of a few %

- $^{27}\text{Mg}$  EC pattern in *p*-GaN:Mg at RT: superposition of 72% substitutional 31% interstitial

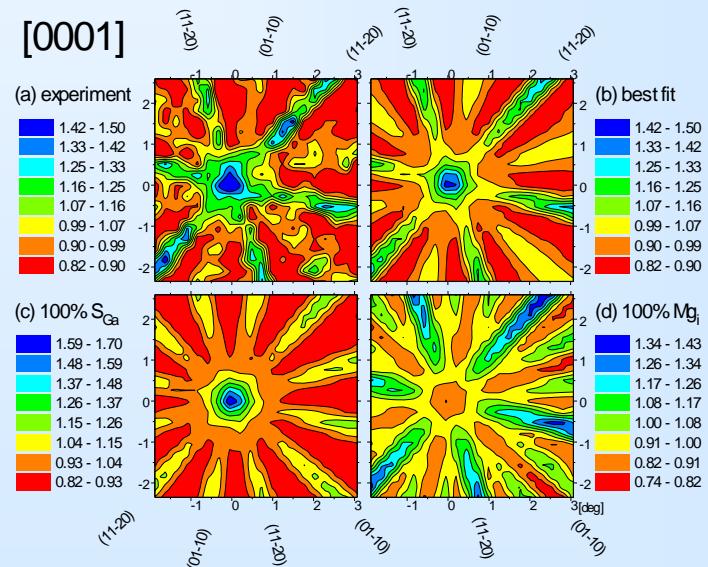
- Studied 4 GaN doping types:

- undoped GaN

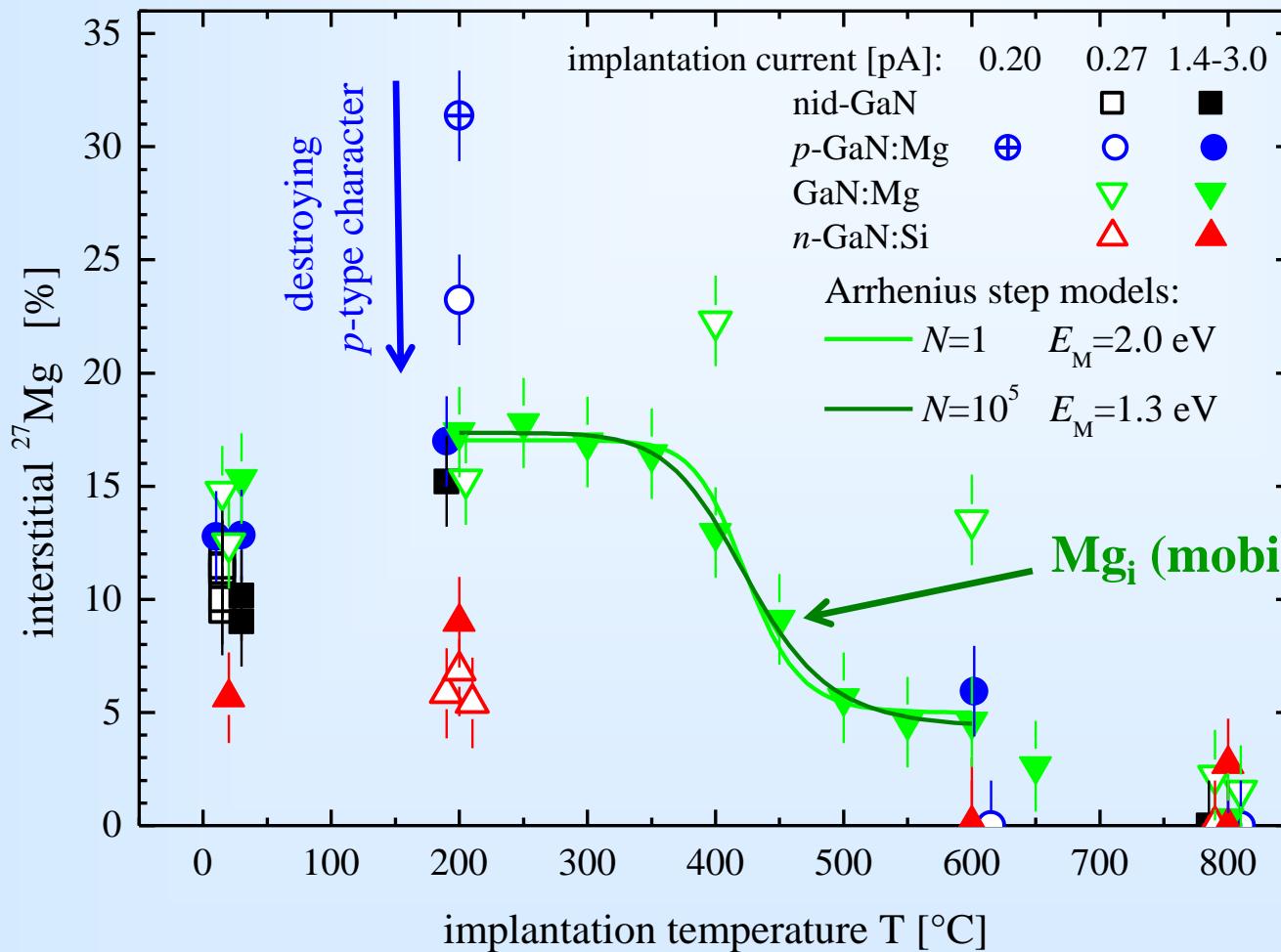
- n*-GaN:Si with  $[\text{Si}] = 10^{19} \text{ cm}^{-3}$

- p*-GaN:Mg with  $[\text{Mg}] = 2 \times 10^{19} \text{ cm}^{-3}$  800°C annealed

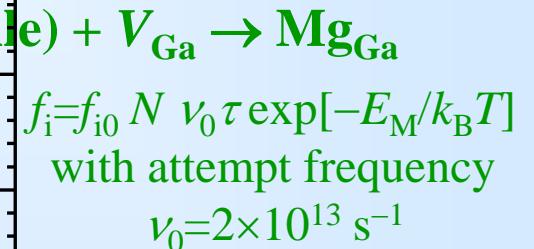
- GaN:Mg with  $[\text{Mg}] = 2 \times 10^{19} \text{ cm}^{-3}$  as grown



# Interstitial $^{27}\text{Mg}$ in different doping types of GaN



1 beam spot  
per sample



- Interstitial  $\text{Mg}_i$  enhanced in *p*-GaN and suppressed in *n*-GaN.
- Site change of  $^{27}\text{Mg}$  from interstitial to substitutional Ga sites as function of implantation temperature allows to estimate activation energy for migration of  $\text{Mg}_i$  as  $E_M \approx 1.3\text{--}2.0 \text{ eV}$ .

# EC-SLI results are being compared to theory already

- Recent theory paper on light group I and II elements in Ga

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## Migration of Mg and other interstitial metal dopants in GaN

Giacomo Miceli\* and Alfredo Pasquarello

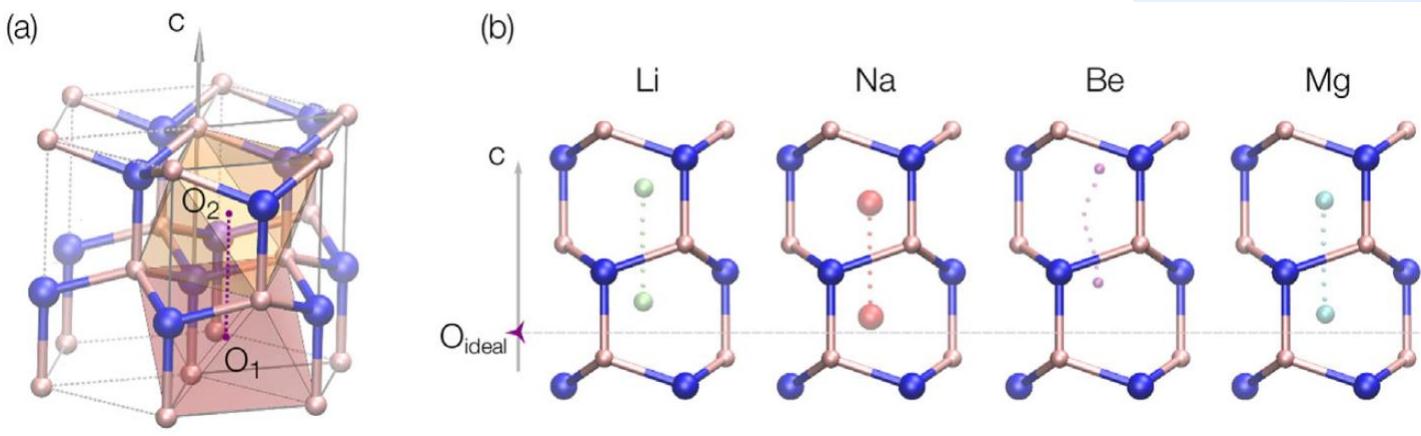
Chaire de Simulation à l'Echelle Atomique (CSEA), Ecole Polytechnique Fédérale de Lausanne (EPFL), CH-1015 Lausanne, Switzerland

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**Table 2** Energy barriers (in eV) for the migration of  $\text{Li}^+$ ,  $\text{Na}^+$ ,  $\text{Be}^{2+}$ , and  $\text{Mg}^{2+}$  along three different diffusion paths.

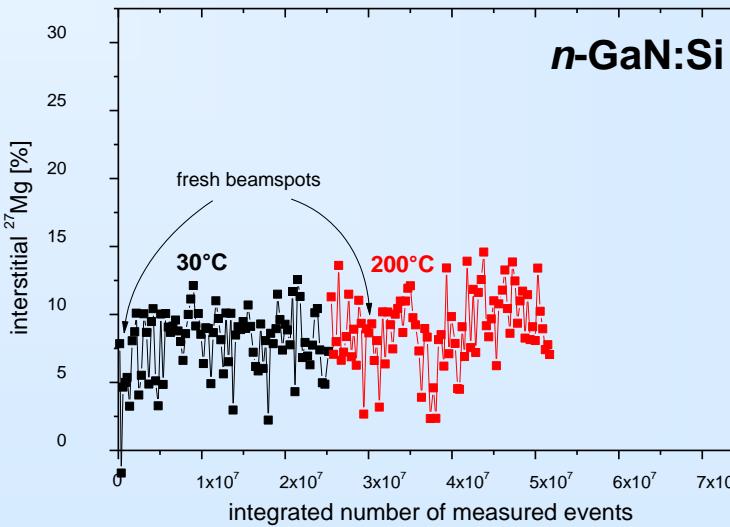
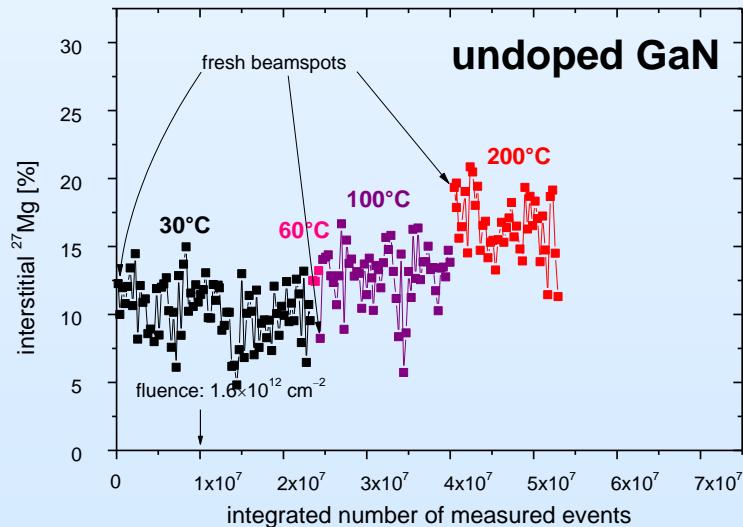
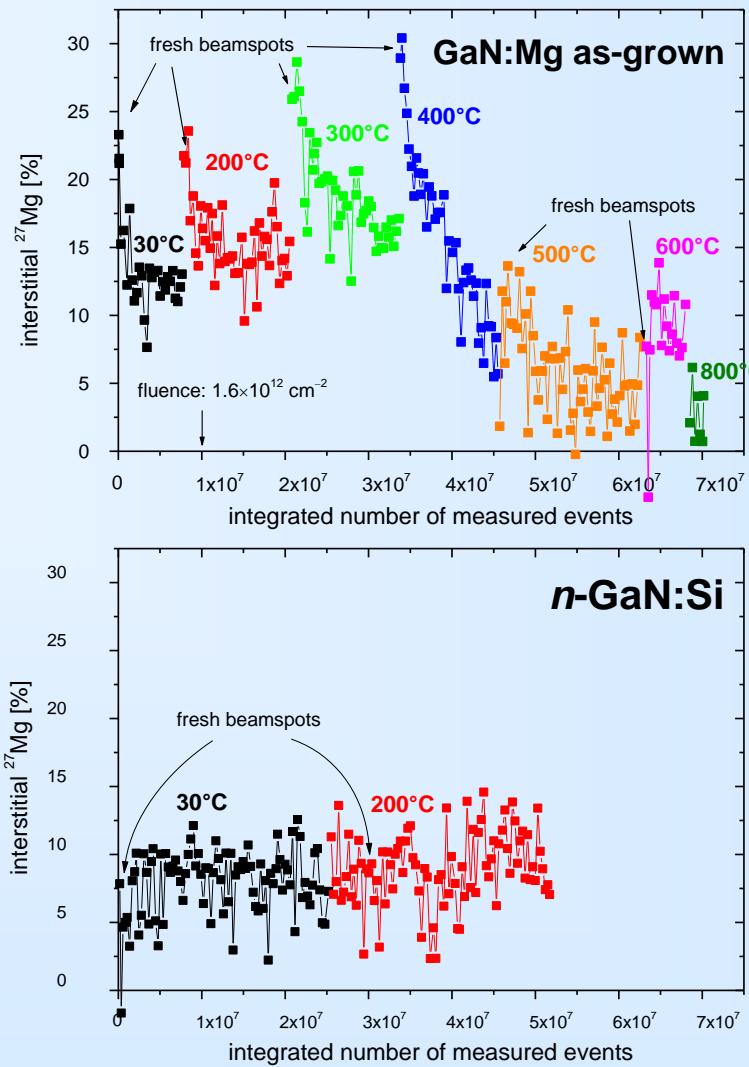
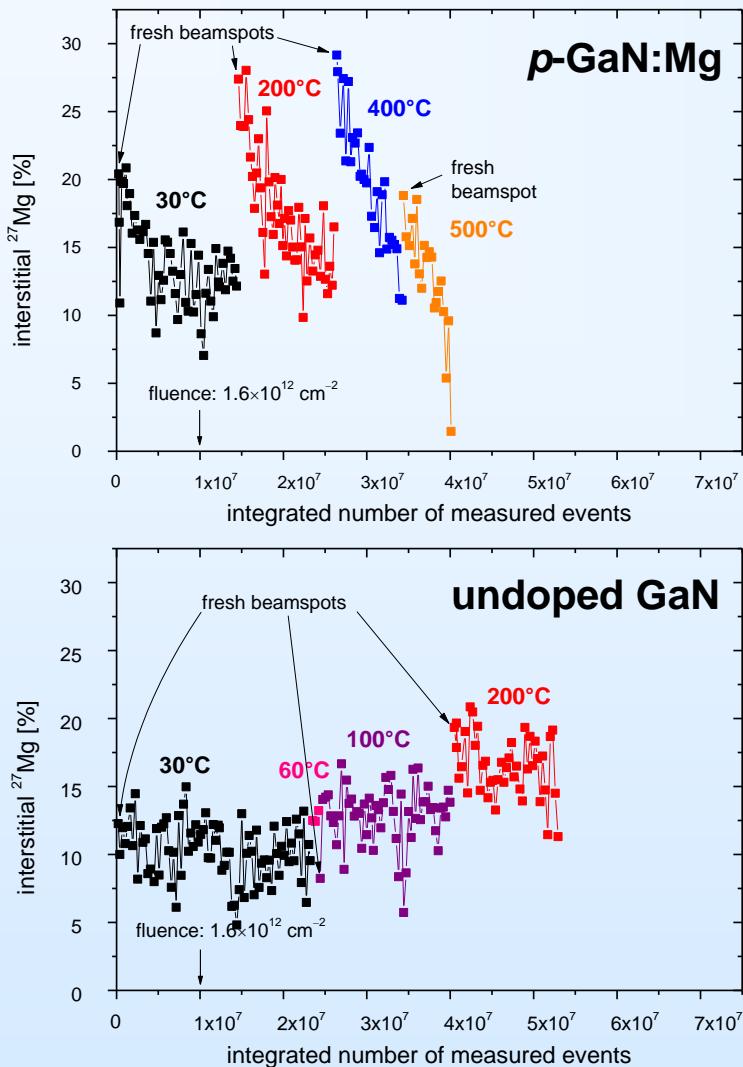
cation	path <i>c</i>	path <i>a</i>	path <i>b</i>
$\text{Li}^+$	1.05	1.16	–
$\text{Na}^+$	2.41	2.95	2.01
$\text{Be}^{2+}$	1.88	0.76	–
$\text{Mg}^{2+}$	2.01	2.20	2.19



- Predicted  $\text{Mg}_i$  site diverts somewhat ( $0.6 \text{ \AA}$ ) from EC-SLI position
- Calculated migration energy (2.01-2.20 eV) at upper end of estimates from EC-SLI (1.3-2.0 eV)

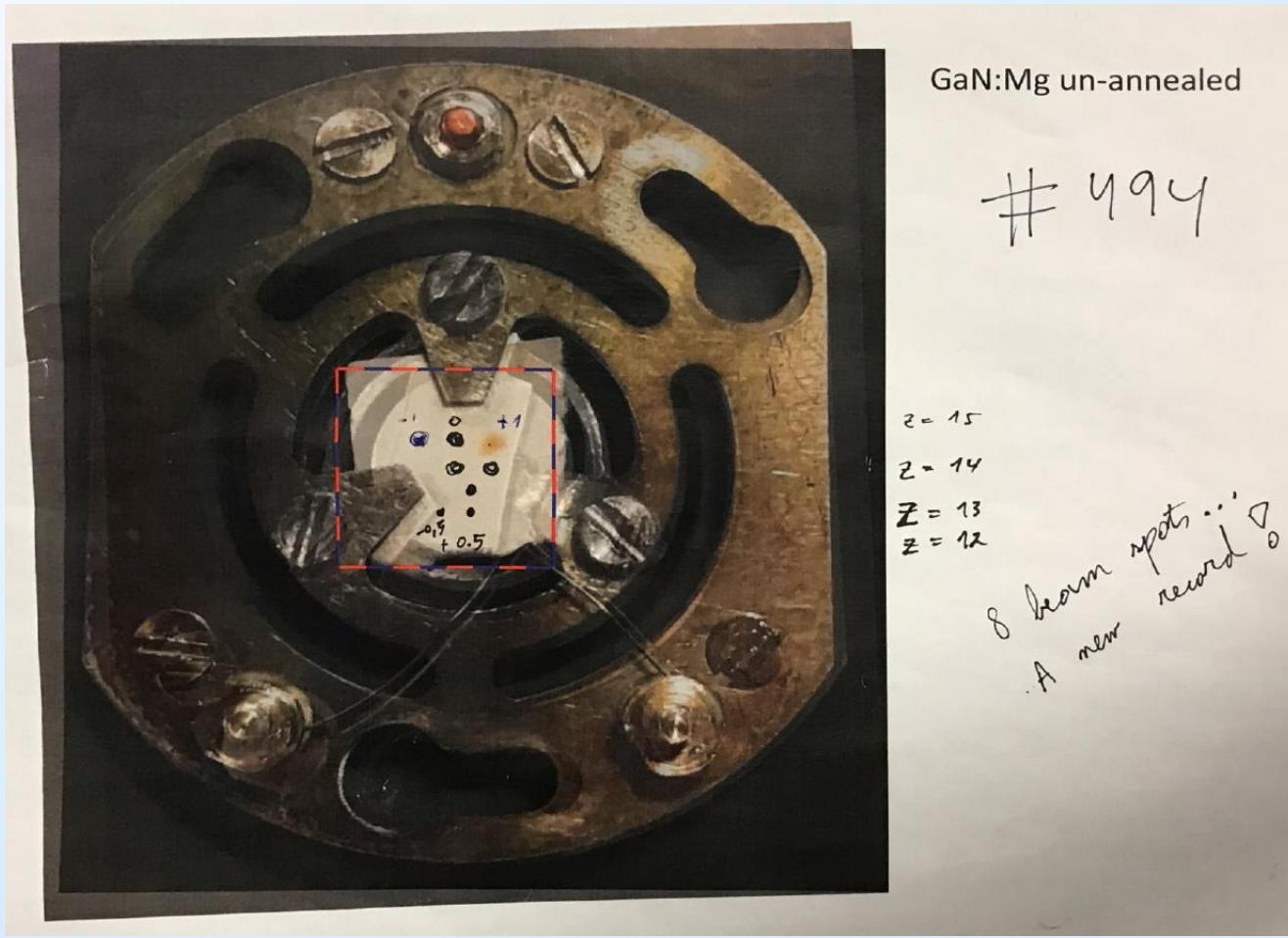
# 2017 results

## Fluence dependence of interstitial $^{27}\text{Mg}$ in different GaN doping types



- Interstitial Mg<sub>i</sub> enhanced in p-GaN and suppressed in n-GaN
- Increase of implantation damage  $\Rightarrow$  interstitial fraction in Mg-doped GaN reaches same levels as in undoped GaN,  $\sim 4\times$  faster in GaN:Mg than in p-GaN:Mg

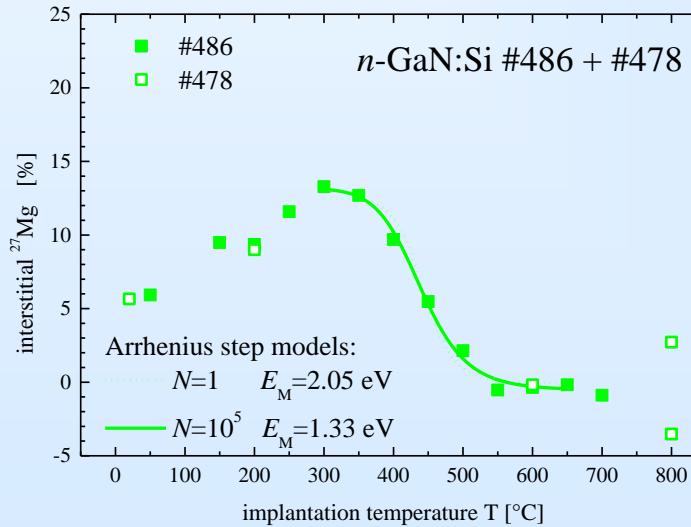
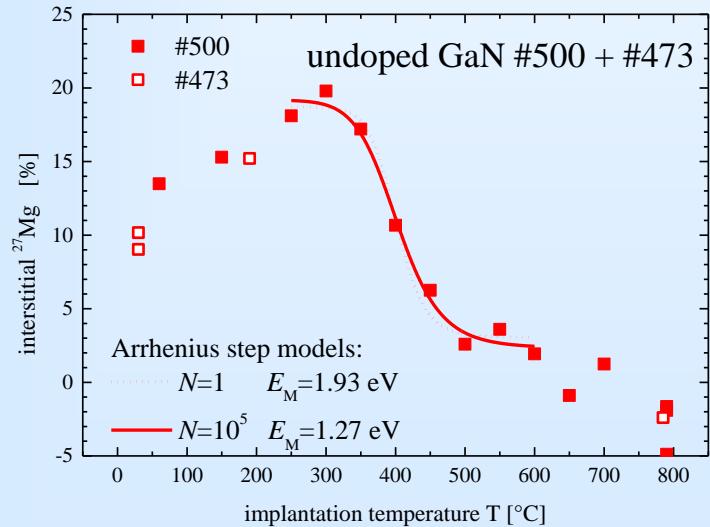
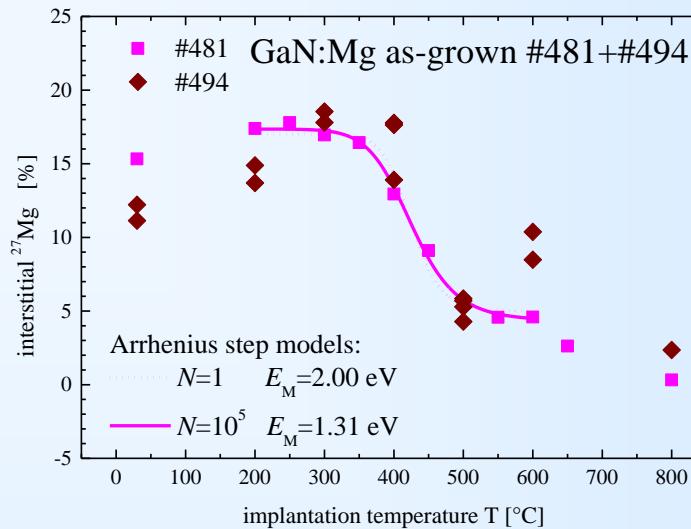
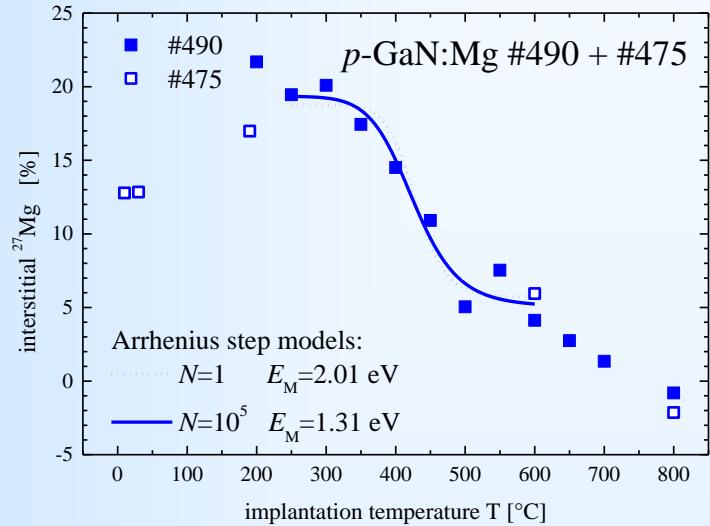
# Fluence dependence of interstitial $^{27}\text{Mg}$ in different GaN doping types



up to 7 beam spots per sample!

2017 results

## Site change $^{27}\text{Mg}_i \rightarrow ^{27}\text{Mg}_{\text{Ga}}$ in different GaN doping types: Arrhenius curves



$$f_i = f_{i0} N \nu_0 \tau \exp[-E_M/k_B T]$$

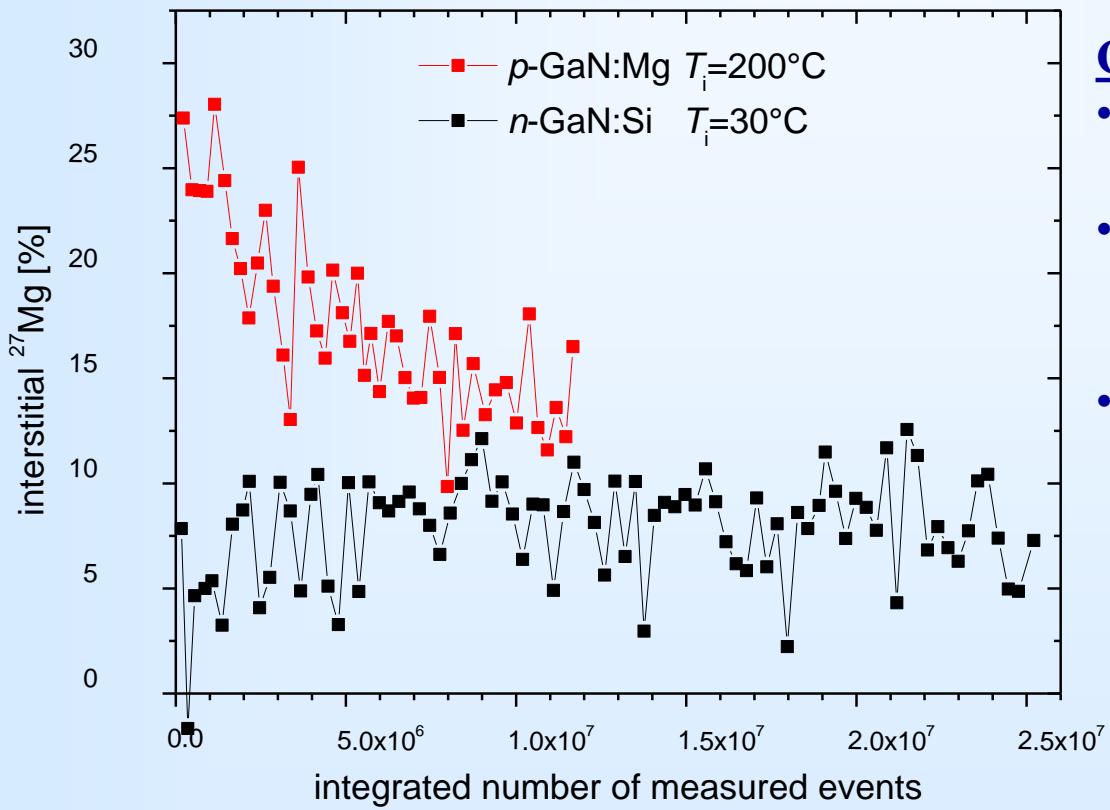
with attempt frequency

$$\nu_0 = 2 \times 10^{13} \text{ s}^{-1}$$

- Estimated activation energy for migration of  $\text{Mg}_i$  in all doping types  $E_M \approx 1.27\text{--}2.01 \text{ eV}$ .
- Number of jumps  $N=10^5$   $E_M \approx 1.3 \text{ eV}$  always fits a bit better...

# Non-statistical fluctuations of Mg<sub>i</sub> fractions

examples of fluence dependence of interstitial  $^{27}\text{Mg}$  in GaN

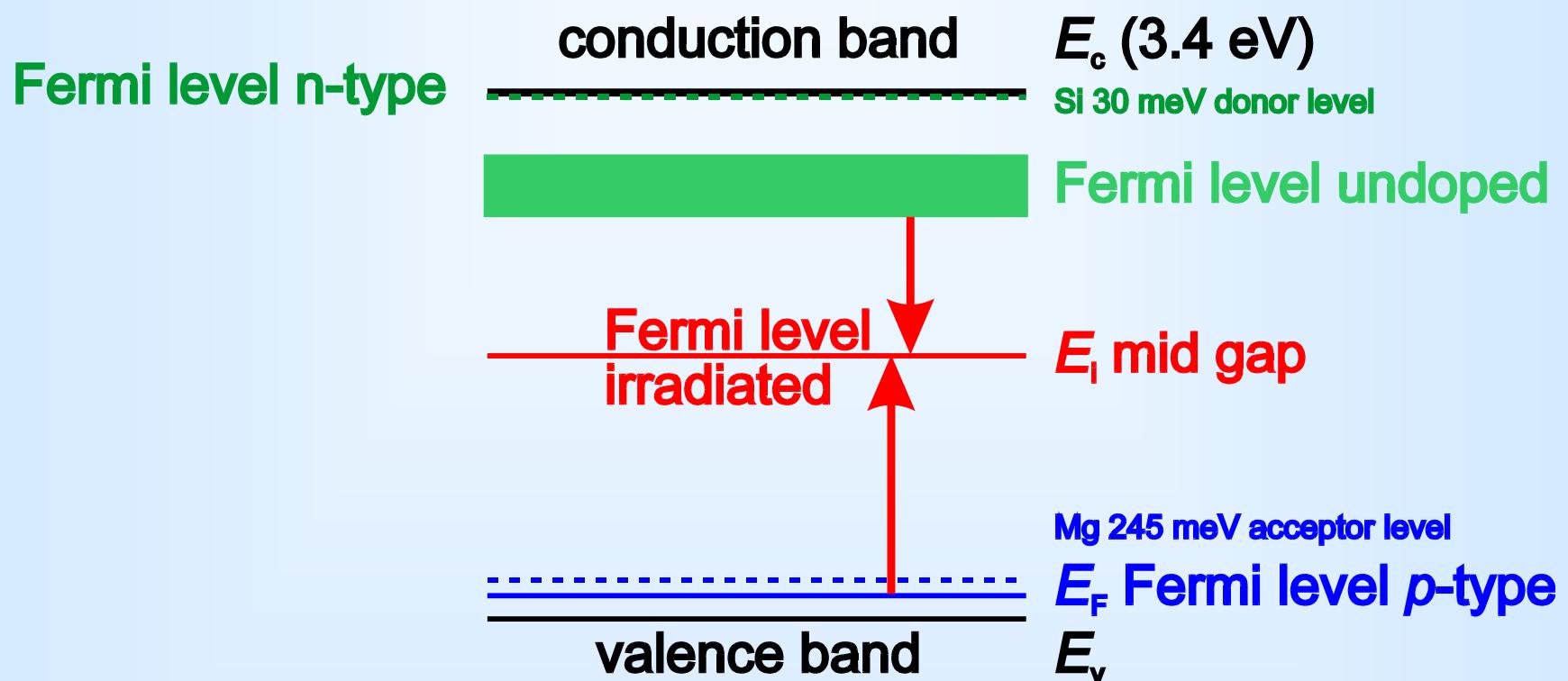


## Charging up caused by:

- implantation current (~0.2-3 pA)
- emission of secondary electrons (~3.5 e<sup>-</sup> per implanted ion)
- outgoing  $\beta^-$  particles

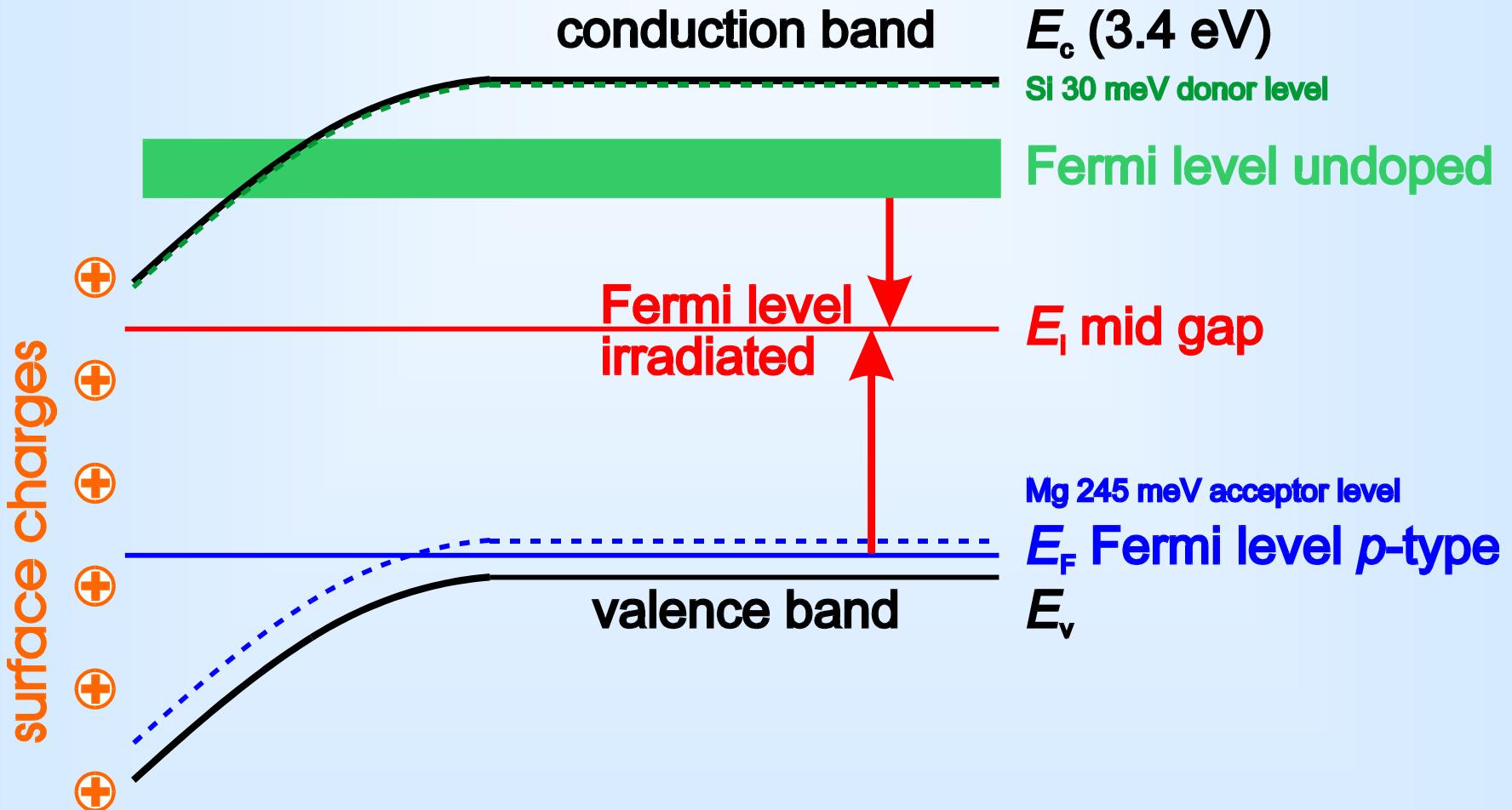
- “Strange” variations in interstitial Mg<sub>i</sub> fractions, e.g. transients, quasi-periodical drops of >5% etc, cannot be explained by statistical fluctuations (should be  $\sim \pm 1\%$ )
- Our explanation: positive charging up of the surface of the GaN sample (GaN thin film deposited on sapphire, a very good insulator)

# Fermi level dependence of Mg lattice site



- Interstitial Mg<sub>i</sub> is most abundant when Fermi level is close to valence band
- Pushing the Fermi level towards mid gap (deep levels resulting from radiation damage) reduces interstitial Mg<sub>i</sub>
- Fermi level close to conduction band gives lowest fractions of interstitial Mg<sub>i</sub>

# Fermi level dependence of Mg lattice site



- Build up of positive surface charges bends the band edges downwards while Fermi level stays constant
- $^{27}\text{Mg}$  probes located in the region of the band bending experience a Fermi level closer to mid gap, hence  $^{27}\text{Mg}_i$  interstitial fraction is reduced

# <sup>11</sup>Be in GaN: a similar case? !

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## Amphoteric Be in GaN: Experimental Evidence for Switching between Substitutional and Interstitial Lattice Sites

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We show that Be exhibits amphoteric behavior in GaN, involving switching between substitutional and interstitial positions in the lattice. This behavior is observed through the dominance of  $\text{Be}_{\text{Ga}}$  in the positron annihilation signals in Be-doped GaN, while the emergence of  $V_{\text{Ga}}$  at high temperatures is a consequence of the Be impurities being driven to interstitial positions. The similarity of this behavior to that found for Na and Li in ZnO suggests that this could be a universal property of light dopants substituting for heavy cations in compound semiconductors.

DOI: 10.1103/PhysRevLett.119.196404

- Clearly an interest in lattice location studies also for Be
- We have already proof of existence of interstitial  $^{11}\text{Be}_i$  at positions ( $-0.66 \pm 0.13$ ) Å from O sites (parasitic experiments in 2012).
- Only RT measured so far. higher temperatures needed for site change  $\text{Be}_i \rightarrow \text{Be}_{\text{Ga}}$  resulting from migration of  $\text{Be}_i$ . Theoretical predictions:  $E_M=1.2\text{-}2.9$  eV [Van de Walle PRB 2001],  $E_M=0.76\text{-}1.88$  eV [Miceli PSSRRL 2017].
- Looking forward to approved experiments with  $^{11}\text{Be}$  to be scheduled in 2018.

# Conclusions

- 2017: full confirmation of amphoteric nature of Mg in GaN
- Interstitial *vs* substitutional Mg fractions depend on
  - Doping type: up to ~30% interstitial Mg<sub>i</sub> found in *p*-GaN, <10% in *n*-GaN
  - Radiation damage: pushes Mg<sub>i</sub> fractions towards situation in undoped GaN
  - Temperature: site change of mobile Mg<sub>i</sub> → Mg<sub>Ga</sub> at 400°C and above
  - Possible influence of surface charges
- Results can be explained based on a Fermi level model
- Looking forward to approved experiments with <sup>11</sup>Be in 2018

Funded by

